	Application No.	Applicant(s)	$\sim$
Notice of Allowability	10/737,227	JEONG ET AL.	$\mathcal{M}$
	Examiner	Art Unit	
	Khanh B. Duong	2822	
The MAILING DATE of this communication appears to the provided the provided to the provided the provided to the provided to the provided the provided to the provided the provided to the provided t	pears on the cover sheet winds (OR REMAINS) CLOSED in Sign of other appropriate communication is sign and MPEP 1308.  July 2005.  The Examiner.  Junder 35 U.S.C. § 119(a)-(d) of the ender according to 37 CF osit of BIOLOGICAL MATE	th the correspondence address this application. If not include unication will be mailed in due of subject to withdrawal from issued for (f).  In No din this national stage application a reply complying with the requestion is deficient.  In MINER'S AMENDMENT or Not declaration is deficient.  In ( PTO-948) attached the Office action of the drawings in the front (not the R 1.121(d).  ERIAL must be submitted. N	d course. THIS e at the initiative of the initiative of the initiative of the course. THIS e at the initiative of the initiative of the course of the initiative of the course of the co
<ul> <li>Attachment(s)</li> <li>1. ⊠ Notice of References Cited (PTO-892)</li> <li>2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)</li> <li>3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date 12/16/03</li> <li>4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ul>	6. ☐ Interview St Paper No./ /08), 7. ⊠ Examiner's	Michael Trini Primary Exam	vance

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04) Art Unit: 2822

# **DETAILED ACTION**

### Election/Restrictions

Applicant's election of Species I (claims 1-7) in the reply filed on July 28, 2005 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

Upon further consideration, Species II (claims 8-20) is determined to be patentably similar to the elected Species I. Thus, claims 8-20, directed to the process of manufacturing a CMOS image sensor using a negative photoresist to form an OCL, previously withdrawn from consideration as a result of a restriction requirement, are now subject to being rejoined. Claims 8-20 are hereby rejoined and fully examined for patentability under 37 CFR 1.104.

Claims 21-32 remain withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected inventions, there being no allowable generic or linking claim.

# **Priority**

Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

# **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

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In the Claims:

Please cancel claims 21-32.

Allowable Subject Matter

Claims 1-20 are allowed.

The following is an examiner's statement of reasons for allowance: none of the prior art of record, taken alone or in combination, fairly shows or suggests all the process limitations as claimed.

Re claim 1, none of the prior art of record discloses a method for manufacturing a CMOS image sensor comprising the following steps in combination with other steps as claimed: d) forming an over-coating layer (OCL) on the color filter array by using a positive photoresist; e) forming openings in the OCL by patterning the OCL by using a binary mask, wherein the binary mask has coated portions and uncoated portions, the uncoated portions being disposed above boundaries between the color filters; and f) forming dome-typed microlenses on a patterned OCL.

Re claim 8, none of the prior art of record discloses a method for manufacturing a CMOS image sensor comprising the following steps in combination with other steps as claimed: d) forming an OCL on the color filter array by using a negative photoresist; e) forming openings in the OCL by patterning the OCL by using a binary mask, wherein the binary mask has coated portions and uncoated portions, the coated portions being disposed above boundaries between the color filters; and f) forming dome-typed microlenses on a patterned OCL.

Re claim 15, none of the prior art of record discloses a method for manufacturing a CMOS image sensor comprising the following steps in combination with other steps as claimed:

d) forming an OCL on the color filter array by using a negative photoresist; e) forming openings in the OCL by patterning the OCL by using a phase shifted mask (PSM), wherein the PSM has a 0° phase and a 180° phase, boundaries between the 0° phase and the 180° phase being disposed above boundaries between the color filters; and forming dome-typed microlenses on a patterned OCL.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

#### Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. The following references disclose relevant teachings regarding processes of forming image sensors: Yamamoto '934, Murakami '668, Fukuyoshi '442, Chang '266 and Murade 778. However, none of these references, taken alone or in combination, fairly shows or suggests all the limitations as claimed.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Khanh B. Duong whose telephone number is (571) 272-1836.

The examiner can normally be reached on 10:00-6:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on (571) 272-1852. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

KBD

Michael Trinh
Primary Examiner
ALFSPE

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